

High temperature mediated rocksalt to wurtzite phase transformation in cadmium oxide nano-sheets and their theoretical evidences

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Table 1S: Inter-planner spacing values from XRD pattern

Sample name	Particle diameter (nm)	2 θ position	Plane	Inter-planner spacing
CdO500	27	33.1	(101)	2.70 Å
		38.4	(200)	2.34 Å
		55.4	(220)	1.66 Å
CdO700	30	33.1	(101)	2.70 Å
		38.4	(200)	2.34 Å
		55.4	(220)	1.66 Å
CdO900	<i>n.a.</i>	37.1	(101)	2.42 Å
		48.6	(102)	1.87 Å

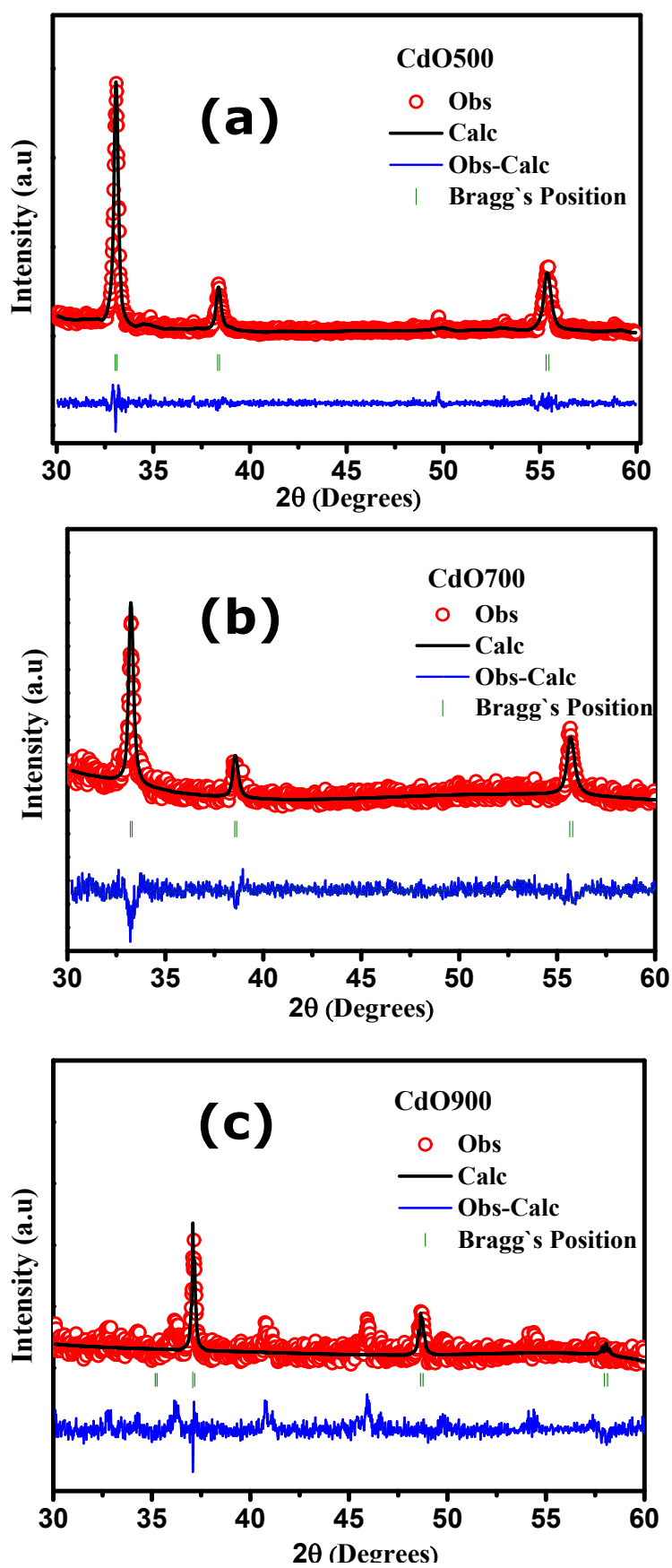


Figure 1S: Rietveld refinement for CdO500, CdO700, CdO900 thin films are shown at (a), (b), (c) respectively

Table 2S: Rietveld refined parameters for various compositions in the system

(a) Results of the Rietveld refinement for CdO500

Cubic phase with space group $Fm-3m$ $a = b = c = 4.69342 (15) \text{ \AA}$, $\alpha = \beta = \gamma = 90^\circ$				
Ions	x	y	z	$B_{iso} (\text{\AA}^2)$
Cd^{2+}	0	0	0	1.002
O^{2-}	0.5	0.5	0.5	1.075
R -factors		$R_p = 14.2$, $R_{w-p} = 19.7$, $R_{exp} = 16.95$, $\chi^2 = 1.35$		

(b) Results of the Rietveld refinement for CdO700

Cubic phase with space group $Fm-3m$ $a = b = c = 4.69342 (15) \text{ \AA}$, $\alpha = \beta = \gamma = 90^\circ$				
Ions	x	y	z	$B_{iso} (\text{\AA}^2)$
Cd^{2+}	0	0	0	1.450
O^{2-}	0.5	0.5	0.5	0.512
R -factors		$R_p = 17.6$, $R_{w-p} = 22.8$, $R_{exp} = 21.18$, $\chi^2 = 1.16$		

(c) Results of the Rietveld refinement for CdO900

Hexagonal phase with space group $P6_3mc$ $a = b = 3.18594 (9) \text{ \AA}$, $c = 5.10303 (7) \text{ \AA}$, $\alpha = \beta = 90^\circ$, $\gamma = 120^\circ$				
Ions	x	y	z	$B_{iso} (\text{\AA}^2)$
$\text{Cd}^{2+} (\text{I})$	0.33330	0.66670	0.99960	1.100
$\text{Cd}^{2+} (\text{II})$	0.66670	0.33330	0.49960	1.100
$\text{O}^{2-} (\text{I})$	0.33330	0.66670	0.38530	0.886
$\text{O}^{2-} (\text{II})$	0.66670	0.33330	0.88530	0.886
R -factors		$R_p = 24.5$, $R_{w-p} = 31.9$, $R_{exp} = 25.43$, $\chi^2 = 1.57$		

Table 3S: Fitting parameters for O 1s and Cd 3d XPS spectra

On surface CdO500 (O 1s)	peak position	peak FWHM	peak area	CdO500 2 nd etching peak position	peak FWHM	peak area	CdO500 4 th etching peak position	peak FWHM	peak area
Cd(OH) ₂ /CdCO ₃	532.07	1.74	12285	531.7	2.05	5497	531.4	2.1	5540
CdO	528.9	1.12	1930	529.0	0.86	6555	529.1	0.96	9903
CdO ₂	529.6	0.87	310.9	529.6	1.28	4707	529.7	0.77	1497
On surface CdO700 (O 1s)	peak position	peak FWHM	peak area	CdO700 2 nd etching peak position	peak FWHM	peak area	CdO700 4 th etching peak position	peak FWHM	peak area
Cd(OH) ₂ /CdCO ₃	532.08	1.76	12105	531.2	2.61	8196	531	3.22	12902
CdO	528.9	1.12	1940	529	0.88	7707	529.1	0.82	6240
CdO ₂	529.6	0.88	299	529.8	0.91	1498	529.7	0.58	656
On surface CdO900 (O 1s)	peak position	peak FWHM	peak area	CdO900 2 nd etching peak position	peak FWHM	peak area	CdO900 4 th etching peak position	peak FWHM	peak area
Cd(OH) ₂ /CdCO ₃	531.8	1.45	8509	531.7	1.44	8303	531.8	1.40	8106
CdO	530.1	1.57	16502	530.1	1.56	17301	530.2	1.59	18782
CdO ₂	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.
On surface CdO500 (Cd 3d)	peak position	peak FWHM	peak area	CdO500 2 nd etching peak position	peak FWHM	peak area	CdO500 4 th etching peak position	peak FWHM	peak area
CdO	404.2	1.19	14519	404.4	1.0	51130	404.4	1.04	52390
CdO ₂	405.2	1.21	6296	405.3	1.6	39863	405.3	1.6	43184
CdCO ₃ /Cd(OH) ₂	405.9	1.22	19820	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.
On surface CdO700 (Cd 3d)	peak position	peak FWHM	peak area	CdO700 2 nd etching peak position	peak FWHM	peak area	CdO700 4 th etching peak position	peak FWHM	peak area
CdO	404.5	1.19	14519	404.4	1.07	50265	404.4	1.38	46065
CdO ₂	405.5	1.21	6296	405.3	1.6	43076	405.5	1.37	33030
CdCO ₃ /Cd(OH) ₂	406.2	1.22	19820	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.
On surface	peak position	peak FWHM	peak area	CdO900 2 nd	peak FWHM	peak area	CdO900 4 th	peak FWHM	peak area

CdO900 (Cd 3d)				etching peak position			etching peak position		
CdO	405.3	1.21	21319	404.8	1.40	63008	404.9	1.41	66314
CdCO ₃ / Cd(OH) ₂	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.	n.a.

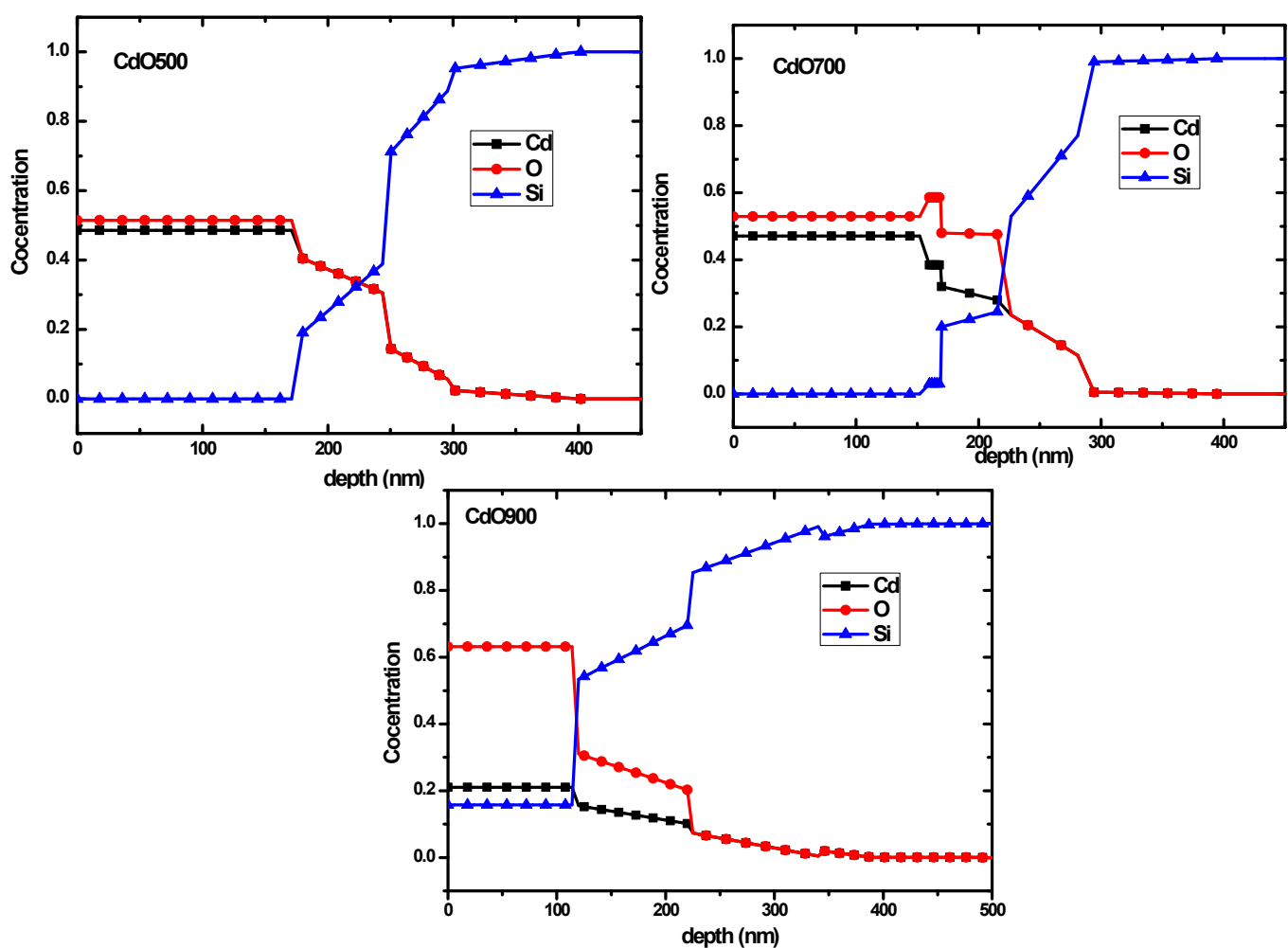


Figure 2S: Depth profiling for CdO500, CdO700, CdO900 thin films

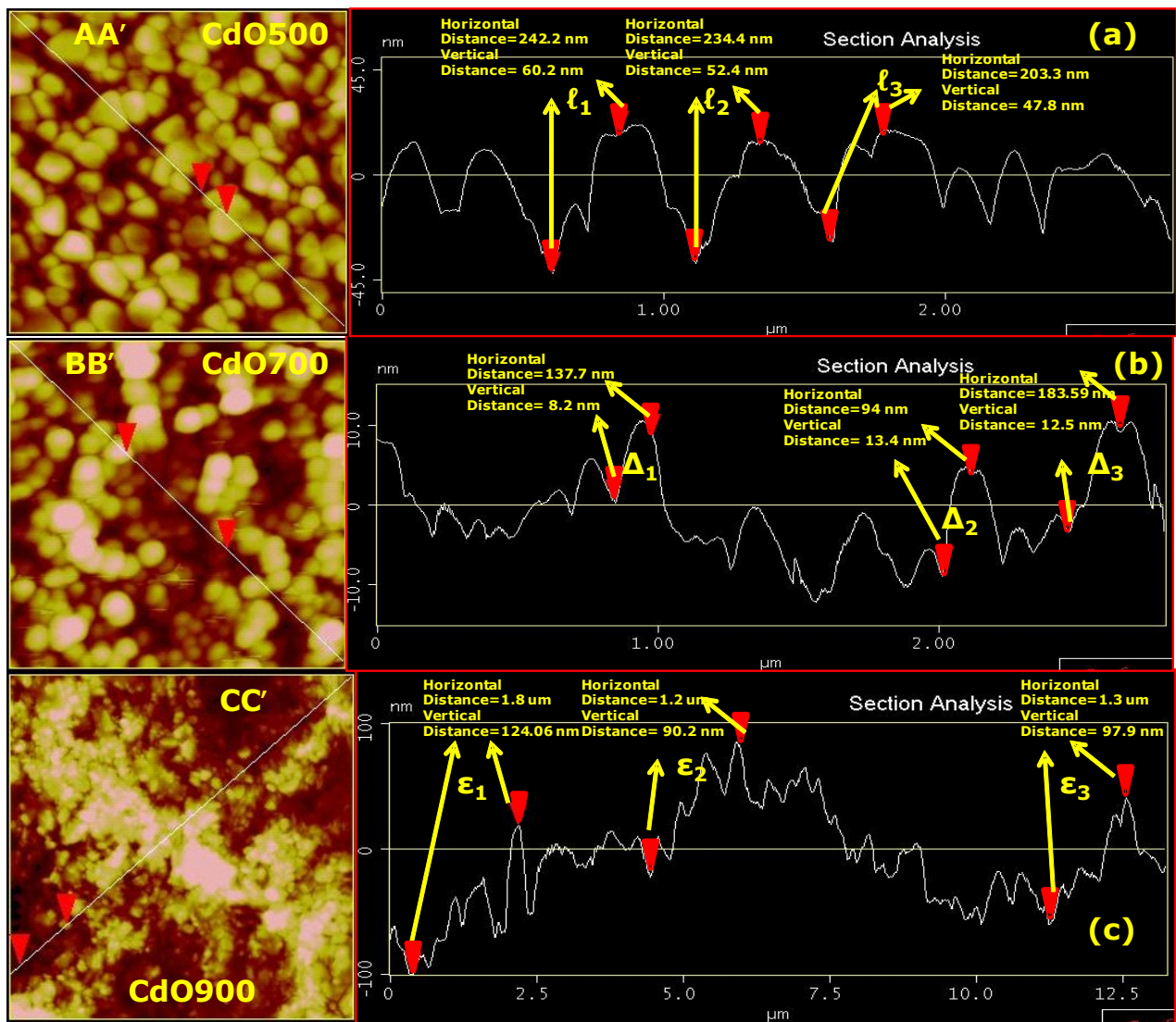


Figure 3S: Section analysis of CdO500, CdO700, CdO900 thin films with nanoscope software

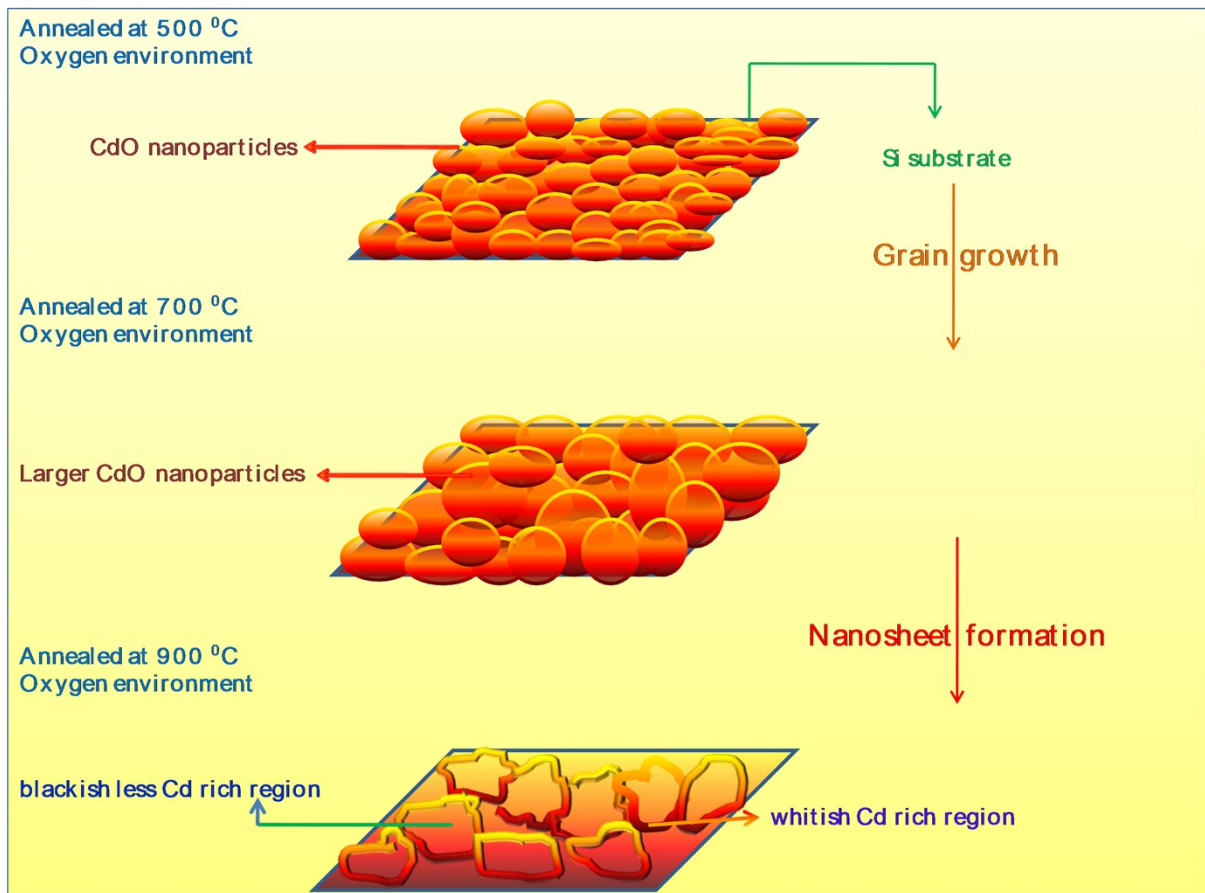


Figure 4S: Schematic illustration of nanosheet formation